













Energy transfer between quantum dots



Particles 2007:Particle-Based Device Technologies How to control the signal. 1.Nanophotonic Switch.(AND-Gate)

ON State



•For the switching operation, we consider three closely spaced cubic quantum dots with Size Ratio =1: $\sqrt{2}$: 2 ·

•In the **OFF** operation, the input energy escapes to the control dot, and then the output signal is obstructed.

•In the **ON** operation, the escape paths are blocked by the excitation of the control dot, and then the input energy goes through the output dot giving an output signal.

•Thus, the nanophotonic switch is realized.



3.The optical nano-fountain using energy transfer between quantum dots



The energy transfer between quantum dots is similar to the energy transfer in the light harvesting system in photosynthetic purple bacteria. (small to large).



Sample for Device Operation CuCl QDs in a NaCl Matrix



CuCl Quantum Cube in a NaCl Matrix

•High density of quantum dots.

•Deep potential depth.

•Nearly perfect cubic shape.





Near-Field Optical Microscopy

For verifying the operation principle of the nanophotonic devices, we selected the material of cubic CuCl quantum dots embedded in a NaCl matrix.

For this sample, the first essential task is to search the coupled quantum dots acting as the nanophotonic devices from the inhomogeneous size dispersed 'sea'.

Optical Near-Field Microscope





Experimental Results: 2.NOT-Gate







These experimental results show this coupled quantum dots system is acting as nanophotonic **NOT-gate**.

Applied physics B Vol. 84, No.1-2,(2006).

Particles 2007: Particle-Based Device Technologies Experimental Results: 3. Nano-fountain Optical nano-fountain Appl. Phys. Lett. 86 103102 (2005). **Intensity Distribution** ainwate 2-10nm. Fountain underground The excitation energy concentrate the largest quantum dot via optical nearfield energy transfer. The largest quantum dot exists The focus diameter was 10 nm. at the focus points. It corresponds to NA≅40 The observed luminescence intensity was as 150 nm The many middle and small sized quantum five times large as luminescence intensity of dots exist at around the focusing position. the isolated single quantum dot.









consumption.

·This small dissipation also supports low power

 \cdot So for NAND operation, we must design it as another total system as NAND-gate.

Performance comparison

Classification	Size:V	Switching time:t _{sw}	Switching Energy:E (/cycle)	ON-OFF Contrast: C	Figure of Merit: C V ⋅ t _{sw} ⋅ E
Optical MEMS	(nλ) ³	1μs	10 ^{-18∼-17} J	10 ⁴	10 ^{-5~-6}
Mach-Zehnder	(nλ) ³	10ps	10 ^{-18∼-17} J	10²	10 ^{-2~-3}
χ ⁽³⁾ non- resonant	(nλ)³	10fs	10 ⁶ photons	10 ³	10 ⁻³
χ ⁽³⁾ resonant	(nλ) ³	1ns	10 ^{3~4} photons	104	10 -4~-5
Quantum well sub-level	(nλ) ³	100fs	10 ^{3~4} photons	10 ³	10 ⁻¹ ~-2
Nanophotonic switch	(λ/10) ³	~100ps	1photon	10	1~

Consideration of thermal problem

Existent electronic device (CPU) 10^9 transistors 1GHz/100W=1 transistor: 10^{-7} W Nanophotonic switch 1GHz/1switch: 10meV × 10^9 /s=10MeV/s= 10^{-12} W

Nanophotonic switch can be integrated 10⁵ times higher density than the existent electronic device (CPU).









Particles 2007: Particle-Based Device Technologies Background & Motivation Nonadiabatic ithography qualitative •Photolithography is the practical highnear-field throughput method to produce electronic and Adiabatic photonic devices •In order to make patterns much smaller, the wavelength of a light source must be shorten, Conventional guantitative 0.001 0.01 0.1 1 (rt. site) 0.001 persion site) 0.001 persion (1.1 site) photolithography I-line due to the diffraction limit G-line Too expensive!! 10 100 1000 Cost of equipment is \$100milion. Wavelength (nm) **Power consumption is 100billion KWh/year in Japan 2005.** We found the Nonadiabatic Photochemical Reaction. Low price of equipments And proposed the photolithography High resolution using the nonadiabatic reaction. Low power consumption (Nonadiabatic photolithography)









Application Nonadiabatic Reaction to Photolithography II

This method increase in the resolution of photolithography. By using 550 nm light, Fabrication of 45nm-L&S was succeeded.







Prototype stepper by Canon Co. LTD. & Univ. Tokyo

Prototype stepper was completed (2006). It has 32nm resolution, but its cost was less than 10% of EUV stepper and EB lithography.

